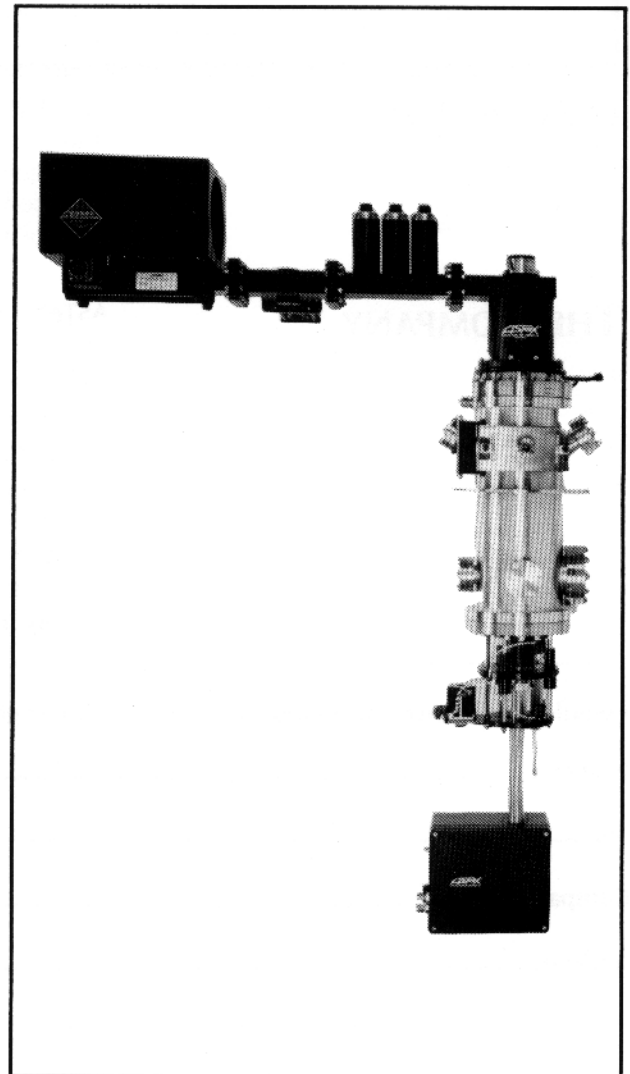
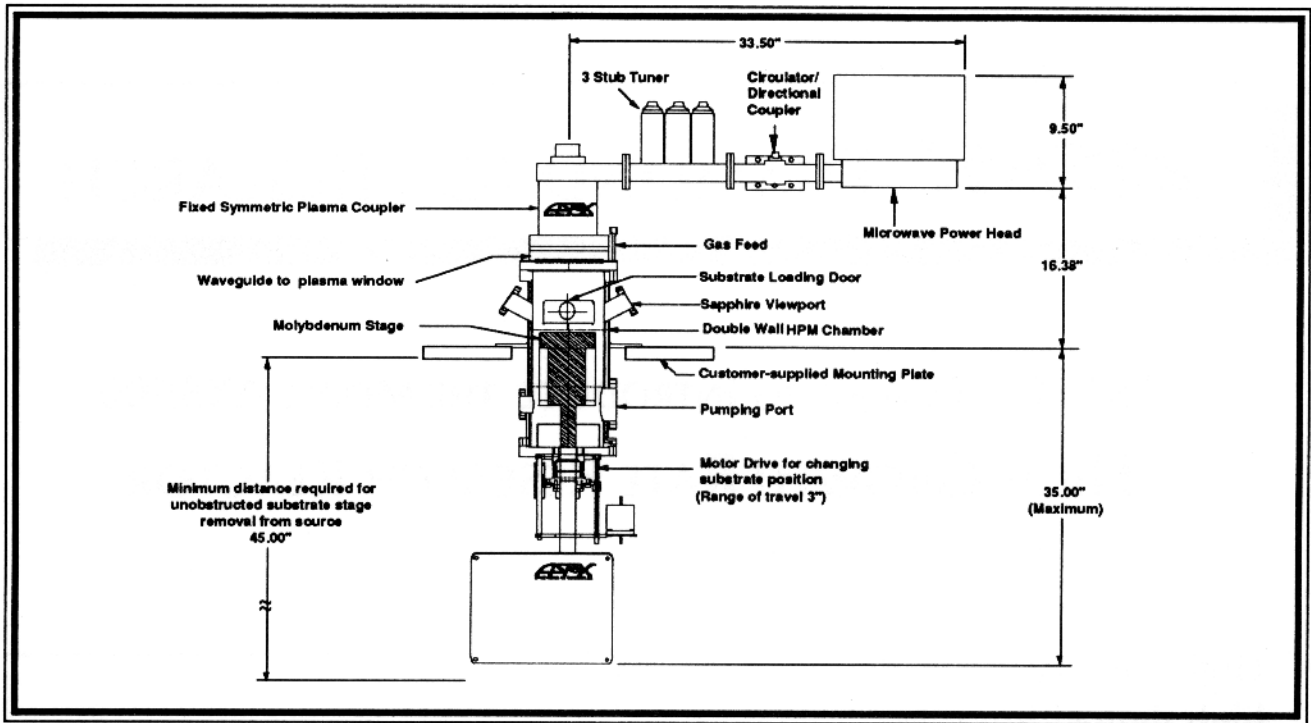


ASTeX IS PLEASED TO INTRODUCE THE MODEL AX5500 HIGH GROWTH RATE RESEARCH REACTOR

- High quality CVD diamond at high deposition rates
- Accommodates substrates up to 1 inch in diameter
- High growth rate process recipes included to provide a quick and successful start to your process development
- Ports provide easy access for diagnostics, manipulators, gas injectors, or filaments, as well as an unobstructed view of the substrate
- The ideal tool for cost effective entry into high growth rate CVD diamond research



Model AX5500
High Growth Rate Research Reactor



DESCRIPTION

The AX5500 includes the reactor chamber, cooled substrate stage, and the ASTeX AX2115 1.5 kW microwave power generator and waveguide components. Process recipes for diamond films are included. The user supplies vacuum pumps, gauges, and gas flow control hardware.

THE COMPANY

ASTeX is a leading supplier of equipment and process technology that enables users to adopt the most sophisticated microwave plasma techniques for processing advanced materials. This equipment includes plasma deposition systems, microwave plasma sources, and microwave power generators. ASTeX has assembled a world-class group of scientists and engineers expert in microwave plasma technology, who are backed up by experienced production, applications, and customer service teams. ASTeX employees are committed to maintaining long-term relationships with customers and using their feedback to provide an ongoing stream of technologically superior products.

I would like further information about the **High Growth Rate Research Reactor:**

Name: _____

Tel: _____ Fax: _____

Company: _____

Address: _____

City: _____ State: _____ Zip: _____ Country: _____

Application: _____